

Ex. Andre' Stevenson

5430548) and (rotate\$2 or rotation\$2 or rotating\$4) and mirror\$2

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5430548

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((5798831)) and (rotate\$2 or rotation\$2 or rotating\$4) and mirror\$2

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(5680207) and (rotate\$2 or rotation\$2 or rotating\$4) and mirror\$2

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(5680207) and (rotate\$2 or rotation\$2 or rotating\$4)

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5680207

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((((5680207) and matrix\$2 and (light\$2 or optical) near (detection or detect\$2 or beam\$2) and linear\$2 near pattern\$2) and (scan\$2 or scanning) and mirror\$2) and (rotate\$2 or rotation\$2 or rotating\$4)

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(((5798831))and (scan\$2 or scanning) and mirror\$2) and (rotate\$2 or rotation\$2 or rotating\$4)

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((5798831)) and (scan\$2 or scanning) and mirror\$2

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(((5680207) and matrix\$2 and (light\$2 or optical) near (detection or detect\$2 or beam\$2) and linear\$2 near pattern\$2) and (scan\$2 or scanning) and mirror\$2

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((6487307)) and (scan\$2 or scanning) and mirror\$2

USPT

(6487307) and defect\$2 and image\$2 and pattern\$2

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(6487307) and defect\$2

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6487307

USPT

(6487307) and defect\$2 and (light\$2 or optical) near (detection or detect\$2 or beam\$2) and (scan\$2 or scanning)and image\$2 and pattern\$2 and linear\$2 near pattern\$2 and matrix\$2

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6487307

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(Semiconductor\$2 and defect\$2 and (light\$2 or optical) near (detection or detect\$2 or beam\$2) and (scan\$2 or scanning)and image\$2 and pattern\$2 and linear\$2 near pattern\$2 and matrix\$2) and light\$2 near beam\$2

USPT

(Semiconductor\$2 and defect\$2 and (light\$2 or optical) near (detection or detect\$2 or beam\$2) and (scan\$2 or scanning)and image\$2 and pattern\$2 and linear\$2 near pattern\$2 and matrix\$2) and light\$2

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Semiconductor\$2 and defect\$2 and (light\$2 or optical) near (detection or detect\$2 or beam\$2) and (scan\$2 or scanning)and image\$2 and pattern\$2 and linear\$2 near pattern\$2 and matrix\$2

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(((5430548) and (second\$2 or two or additional\$2) near (patteren\$2 or wafer\$2 or work\$2) and defect\$2) and (second\$2 or two or additional\$2)

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(((5798831) and matrix\$2 and (light\$2 or optical) near (detection or detect\$2 or beam\$2) and linear\$2 near pattern\$2) and defect\$2) and (second\$2 or two or additional\$2)

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(((5680207) and matrix\$2 and (light\$2 or optical) near (detection or detect\$2 or beam\$2) and linear\$2 near pattern\$2) and defect\$2) and (second\$2 or two or additional\$2)

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((5430548) and (second\$2 or two or additional\$2) near (patteren\$2 or wafer\$2 or work\$2)) and defect\$2

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((5798831) and matrix\$2 and (light\$2 or optical) near (detection or detect\$2 or beam\$2) and linear\$2 near pattern\$2) and defect\$2

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((5680207) and matrix\$2 and (light\$2 or optical) near (detection or detect\$2 or beam\$2) and linear\$2 near pattern\$2) and defect\$2

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((5680207) and matrix\$2 and (light\$2 or optical) near (detection or detect\$2 or beam\$2) and linear\$2 near pattern\$2) and (second\$2 or two or additional\$2) near (patteren\$2 or wafer\$2 or work\$2)

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((5798831) and matrix\$2 and (light\$2 or optical) near (detection or detect\$2 or beam\$2) and linear\$2 near pattern\$2) and (second\$2 or two or additional\$2) near (patteren\$2 or wafer\$2 or work\$2)

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(5430548) and (second\$2 or two or additional\$2) near (patteren\$2 or wafer\$2 or work\$2)

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(5798831) and matrix\$2 and (light\$2 or optical) near (detection or detect\$2 or beam\$2) and linear\$2 near pattern\$2

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(5680207) and matrix\$2 and (light\$2 or optical) near (detection or detect\$2 or beam\$2) and linear\$2 near pattern\$2

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(5430548) and matrix\$2 and (light\$2 or optical) near (detection or detect\$2 or beam\$2) and linear\$2 near pattern\$2

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(5798831) and matrix\$2 and (light\$2 or optical) near (detection or detect\$2 or beam\$2) and linear\$2 near pattern\$2

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((((((Semiconductor\$2 and defect\$2 near inspection\$2)and (light\$2 or optical) near (detection or detect\$2 or beam\$2))and (scan\$2 or scanning))and image\$2 and pattern\$2)and linear\$2 near pattern\$2) and matrix\$2)

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(((((Semiconductor\$2 and defect\$2 near inspection\$2)and (light\$2 or optical) near (detection or detect\$2 or beam\$2))and (scan\$2 or scanning))and image\$2 and pattern\$2)and linear\$2 near pattern\$2) and matrix\$2

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((((Semiconductor\$2 and defect\$2 near inspection\$2)and (light\$2 or optical) near (detection or detect\$2 or beam\$2))and (scan\$2 or scanning))and image\$2 and pattern\$2) and matrix\$2

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((5430548) and defect\$2) and (second\$2 or two or additional\$2) near (patteren\$2 or wafer\$2 or work\$2)

USPT (5430548) and defect\$2

USPT 5430548

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(((((Semiconductor\$2 and defect\$2 near inspection\$2) and (light\$2 or optical) near (detection or detect\$2 or beam\$2)) and (scan\$2 or scanning)) and image\$2 and pattern\$2) and linear\$2 near pattern\$2) and (second\$2 or two or additional\$2) near (patteren\$2 or wafer\$2 or work\$2)

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((((Semiconductor\$2 and defect\$2 near inspection\$2)and (light\$2 or optical) near (detection or detect\$2 or beam\$2))and (scan\$2scanning))and image\$2 and pattern\$2) and linear\$2 near pattern\$2

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(((Semiconductor\$2 and defect\$2 near inspection\$2)and (light\$2 or optical) near (detection or detect\$2 or beam\$2))and (scan\$2 or scanning)) and image\$2 and pattern\$2

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(((Semiconductor\$2 and defect\$2 near inspection\$2)and (light\$2 or optical) near (detection or detect\$2 or beam\$2))and (scan\$2 or scanning)) image\$2 and pattern\$2

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(((Semiconductor\$2 and defect\$2 near inspection\$2)and (light\$2 or optical) near (detection or detect\$2 or beam\$2))and (scan\$2 or scanning)) image

USPT

((Semiconductor\$2 and defect\$2 near inspection\$2)and (light\$2 or optical) near (detection or detect\$2 or beam\$2)) and (scan\$2 or scanning)

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(Semiconductor\$2 and defect\$2 near inspection\$2) and (light\$2 or optical) near (detection or detect\$2 or beam\$2)

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Semiconductor\$2 and defect\$2 near inspection\$2